

290. PTB-Seminar VUV and EUV Metrology

PTB Berlin

Abbestr. 2-12
10587 Berlin

Hermann-von-
Helmholtz Building

Day 2: Friday 06.11.2015

Time	Speaker	Title	Institute/ Company
8:30		Opening of Day 2	
Session IV: Scatter techniques			
8:40	V. Holy	Diffuse x-ray reflection from randomly rough multilayers - beyond the standard fractal model	U Prague
9:00	A. Haase	Interface properties of multilayer mirrors with sub-nanometer layer thicknesses	PTB
9:20	A. Maryasov	EUV scattering metrology with high-brightness discharge plasma source	RWTH
9:40	S. Heidenreich	Comparison of sampling methods and application to scatterometry	PTB
10:00	Coffee Break		
Session V: Spectroscopy & Surfaces			
10:40	E. teSlighte	EBL2, a flexible and controlled EUV exposure and surface analysis system	TNO
11:00	D. Bleiner	Concomitant surface microscopy and spectroscopy in the lab enabled by plasma-driven XUV	EMPA
11:20	I. Mantouvalou	Novel Spectroscopic Schemes using a Highly Brilliant Laser-Produced Plasma Source	TUB
11:40	J.I. Larruquert	Optical-constant metrology of VUV thin-film materials	CSIC
12:00	Lunch		
Session VI: Optics & Materials			
13:20	T. Feigl	EUV optics with integrated IR suppression gratings	Optixfab
13:40	A. Gatto	Last developments for high end optical gratings and microstructured optics	CZ Jena
14:00	F. Siewert	On the characterization of ultra-precise mirrors for use at FEL-beamlines by use of slope measuring	HZB
14:20	E. Meltchakov	Design, deposition and metrology of EUV multilayer coatings for SR, FEL and space applications	IO/LCF
14:40	K. Nikolaev	High resolution X-ray diffraction in extremely asymmetrical condition	U Twente
15:00	S. Yulin	Interface-engineered EUV/Soft X-ray multilayer mirrors	IOF
15:20	A. Gottwald	Wrap-up and Closing	PTB
15:30	End of the Seminar		